Author Index for Papers in Volume 21

Pages are numbered consecutively through the volume: 1-96, January; 97-208, March; 209-304, May; 305-400, July; 401-496, September; and 497-598, November. Communications are identified by (C) and Letters to the Editor by (L).

Albrecht, D. M., E. G. Laenen, and Chua Lin, Experiments on the Dynamic Response of a Flexible Strip to Moving Loads (C) 379
Arnett, P. C., see DiMaria, D. J. 227
Ashley, C. T., K. E. Edds, and D. L. Elbert, Development and Characterization of Ink for an Electrostatic Ink Jet Printer 69

Beach, B. L., C. W. Hildenbrandt, and W. H. Reed, Materials Selection for an Ink Jet Printer 75
Bennett, B. T., and P. A. Franaszek, Permutation Clustering: An Approach to On-Line Storage Reorganization 528
Bernstein, P. A., see Delobel, C. 484
Berry, B. S., and J. R. Susko, Solubility and Diffusion of Sulfur in Polymeric Materials 176
Buehner, W. L., J. D. Hill, T. H. Williams, and J. W. Woods, Application of Ink Jet Technology to a Word Processing Output Printer 2
Buehner, W. L., see Fillmore, G. L. 37

Carmichael, J. M., Controlling Print Height in an Ink Jet Printer 52
Casey, R. G., see Delobel, C. 484
Chaitin, G. J., Algorithmic Information Theory 350
Errata 496
Chamberlin, D. D., Erratum: SEQUEL 2: A Unified Approach to Data Definition, Manipulation, and Control (Vol. 20, No. 6, p. 560) 94
Chow, W. M., and L. Woo, Buffer Performance Analysis of Communication Processors During Slowdown at Network Control 264
Cuomo, J. J., R. J. Gambino, J. M. E. Harper, and J. D. Kuptsis, Origin and Effects of Negative Ions in the Sputtering of Intermetallic Compounds (C) 580
Curry, S. A., and H. Portig, Scale Model of an Ink Jet 10

Davies, J. E., Control of Magnetic Properties During the Processing of Single Crystal Garnet Films 522
Davis, D. E., R. D. Moore, M. C. Williams and O. C. Woodard, Automatic Registration in an Electron-Beam Lithographic System 498
Delobel, C., R. G. Casey, and P. A. Bernstein, Comment on "Decomposition of a Data Base and the Theory of Boolean Switching Functions" (L) 484
Dill, F. H., and J. M. Shaw, Thermal Effects on the Photoresist AZ1350J 210
Dill, F. H., see Shaw, J. M. 219
DiMaria, D. J., and P. C. Arnett, Conduction Studies in Silicon Nitride: Dark Currents and Photocurrents 227

Edds, K. E., see Ashley, C. T. 69
Elbert, D. L., see Ashley, C. T. 69
Engelke, H., J. F. Loughran, M. S. Michail, and P. M. Ryan, Correction of Nonlinear Deflection Distortion in a Direct Exposure Electron-Beam System 506

Fagin, R., Functional Dependencies in a Relational Data Base and Propositional Logic 534
Feliss, N. A., and F. E. Talke, Capacitance Probe Study of Rotating-Head/Tape Interface (C) 289
Fernández, E. B., see Lang, T. 273
Fillmore, G. L., W. L. Buehner, and D. L. West, Drop Charging and Deflection in an Electrostatic Ink Jet Printer 37
Fischer, J., see Swalen, J. D. 168
Fleischer, J. M., M. R. Latta, and M. E. Rabedeau, Laser-Optical System of the IBM 3800 Printer (C) 479
Franaszek, P. A., see Bennett, B. T. 528
Fratta, L., see Maruyama, K. 360
Frisch, M. A., see Shaw, J. M. 219
Furtney, R., see Kiwimagi, R. 340

Gambino, R. J., see Cuomo, J. J. 580
Gaur, S. P., Safe Operating Area for Bipolar Transistors 433
Gaur, S. P., Two-Dimensional Analysis of High-Voltage Power Transistors 306
Gipstein, E., A. C. Ouano, D. E. Johnson, and O. U. Need, III, Parameters Affecting the Electron Beam Sensitivity of Poly(methyl methacrylate) 143
Greene, R. L., see Street, G. B. 99
Griffiths, L., see Kiwimagi, R. 340

Harper, J. M. E., see Cuomo, J. J. 580
Herbst, N. M., and C. N. Liu, Automatic Signature Verification Based on Accelerometry 245
Hildenbrandt, C. W., see Beach, B. L. 75
Hill, J. D., see Buehner, W. L. 2
Hiraoka, H., Radiation Chemistry of Poly(methacrylates) 121

Inselberg, A., Variable Geometry Cochlear Model at Low Input Frequencies: A Basis for Compensating Morphological Disorders 461

Johnson, D. E., see Gipstein, E 143

Kiwimagi, R., L. Griffiths, and R. Furtney, Worst-Case Pattern Evaluation of Baseband Channels 340
Kou, L. T., and G. Markowsky, Multidimensional Bin Packing Algorithms 443
Kuptsis, J. D., see Cuomo, J. J. 580

Laenen, E. G., see Albrecht, D. M. 379
Lam, S. S., An Extension of Moore's Result for Closed Queuing Networks (C) 384
Lam, S. S., Queuing Networks with Population Size Constraints 370
Erratum 598

Lang, T., and E. B. Fernández, Improving the Computation of Lower Bounds for Optimal Schedules 273
Latta, M. R., see Fleischer, J. M. 479
Lavenberg, S. S., and C. H. Sauer, Sequential Stopping Rules for the Regenerative Method of Simulation 545
Lee, H. C., Boundary Layer Around a Liquid Jet 48
Lee, H. C., see Pimbley, W. T. 21
Lee, H. S., Analysis of the Merged Charge Memory (MCM) Cell 402
Levanoni, M., Study of Fluid Flow through Scaled-up Ink Jet Nozzles 56
Lieberman, L. I., and M. A. Wesley, AUTOPASS: An Automatic Programming System for Computer Controlled Mechanical Assembly 321
Lin, Chua, see Albrecht, D. M. 379
Liu, C. N., see Herbst, N. M. 245
Lomet, D. B., Data Flow Analysis in the Presence of Procedure Calls 559
Loughran, J. F., see Engelke, H. 506
Lyerla, J. R., Jr., NMR Study of the Chain Microstructure of P(MMA-co-MAA) 111

Markowski, G., see Kou, L. T. 443
Maruyama, K., and D. T. Tang, Discrete Link Capacity and Priority Assignments in Communication Networks 254
Maruyama, K., L. Fratta, and D. T. Tang, Heuristic Design Algorithm for Computer Communication Networks with Different Classes of Packets 360
Matino, H., and T. Ushiroda, Effect of Substrate Bias on Properties of RF-Sputtered Cr-SiO Films (C) 576
Mauer, J. L., H. C. Pfeiffer, and W. Stickel, Electron Optics of an Electron-Beam Lithographic System 514
Michail, M. S., see Engelke, H. 506
Moore, R. D., see Davis, D. E. 498

Need, O. U., III, see Gipstein, E. 143
Nussbaumer, H. J., Linear Filtering Technique for Computing Mersenne and Fermat Number Transforms 334

Ouano, A. C., see Gipstein, E. 143
Ouano, A. C., see Tu, Y. O. 131

Peters, R. J., Zero Order and Nonzero Order Decision Rules in Medical Diagnosis 449
Pfeiffer, H. C., see Mauer, J. L. 514
Pimbley, W. T., and H. C. Lee, Satellite Droplet Formation in a Liquid Jet 21
Portig, H., see Curry, S. A. 10

Rabedeau, M. E., see Fleischer, J. M. 479
Reed, W. H., see Beach, B. L. 75
Roth, J. P., see Traub, R. D. 572
Ryan, P. M., see Engelke, H. 506

Santo, R., see Swalen, J. D. 168
Sauer, C. H., see Lavenberg, S. S. 545
Shaw, J. M., M. A. Frisch, and F. H. Dill, Thermal Analysis of Positive Photoresist Films by Mass Spectrometry 219
Shaw, J. M., see Dill, F. H. 210
Smith, T. L., Strength and Related Properties of Elastomeric Block Copolymers 154
Stickel, W., see Mauer, J. L. 514
Street, G. B., and R. L. Greene, Preparation and Properties of $(SN)_x$ 99
Susko, J. R., see Berry, B. S. 176
Swalen, J. D., R. Santo, M. Tacke, and J. Fischer, Properties of Polymeric Thin Films by Integrated Optical Techniques .. 168

Tacke, M., see Swalen, J. D. 168
Talke, F. E., see Feliss, N. A. 289
Tang, D. T., see Maruyama, K. 254
Tang, D. T., see Maruyama, K. 360
Tang, D. T., see Wong, C. K. 281
Traub, R. D., and J. P. Roth, Potential Significance to Neurophysiology of Design Algorithms for Digital Computers (C) 572
Tu, Y. O., and A. C. Ouano, Model for the Kinematics of Polymer Dissolution 131
Twardeck, T. G., Effect of Parameter Variations on Drop Placement in an Electrostatic Ink Jet Printer 31

Ushiroda, T., see Matino, H. 576

van de Lindt, W. J., Digital Technique for Generating Synthetic Aperture Radar Images 415

Washo, B. D., Rheology and Modeling of the Spin Coating Process 190
Wesley, M. A., see Lieberman, L. I. 321
West, D. L., see Fillmore, G. L. 37
Williams, M. C., see Davis, D. E. 498
Williams, T. H., see Buehner, W. L. 2
Wong, C. K., and D. T. Tang, Dynamic Memories with Faster Random and Sequential Access 281
Woo, L., see Chow, W. M. 264
Woodard, O. C., see Davis, D. E. 498
Woods, J. W., see Buehner, W. L. 2

Zable, J. L., Splatter During Ink Jet Printing 315

Subject Index for Papers in Volume 21

Each index term below is accompanied by a page number and an author's name. With that name in the Author Index are the title of the paper and the names of coauthors, if any. Communications are identified by (C) and Letters to the Editor by (L).

Subject	*Author*	*Page*
Algorithms		
Bin packing	Kou	443
Cochlear model	Inselberg	461
Communication network assignments	Maruyama	254
Computation of lower bounds	Lang	273
Information theory	Chaitin	350
Errata	Chaitin	496
Heuristic network design	Maruyama	360
Network control	Chow	264
Queuing networks	Lam	370
Erratum	Lam	598
Queuing networks (C)	Lam	384
Radar images	van de Lindt	415
Regenerative simulation	Lavenberg	545
Analytical models		
Bin packing	Kou	443
Closed queuing networks (C)	Lam	384
Population size constraints	Lam	370
Erratum	Lam	598
Worse-case pattern evaluation of baseband channels	Kiwimagi	340
Chemistry and chemical engineering		
Ink jet printer materials	Beach	75
Jet printer ink	Ashley	69
Circuit technology		
Digital filter	Nussbaumer	334
High-voltage power transistors	Gaur	306
Merged charge memory cell	Lee	402
Photoresist analysis	Shaw	219
Photoresists	Dill	210
Safe operating area for bipolar transistors	Gaur	433
Sputtered Cr-SiO films (C)	Matino	576
Codes and coding		
Worse-case pattern evaluation of baseband channels	Kiwimagi	340
Communication networks		
Design algorithm	Maruyama	360
Priority assignments	Maruyama	254
Compilers and compiling		
Computer controlled assembly	Lieberman	321
Data flow analysis	Lomet	559
Computation method		
Information theory	Chaitin	350
Errata	Chaitin	496
Number transforms	Nussbaumer	334
Data structures and accessing		
Comment on data base decomposition (L)	Delobel	484
Dynamic memories	Wong	281
Functional dependencies	Fagin	534
SEQUEL 2 language (Vol. 20, No. 6) Erratum	Chamberlin	94
Electron beams		
Automatic registration	Davis	498
Correction of nonlinear distortion	Engelke	506
Electron beam sensitivity of PMMA	Gipstein	143
Electron optics	Mauer	514
Electrophotography		
Laser-optical system (C)	Fleischer	479
Films		
Negative ions in sputtering (C)	Cuomo	580
Polymeric properties by optical techniques	Swalen	168
Single crystal garnet processing	Davies	522
Sputtered Cr-SiO films (C)	Matino	576
Fluid dynamics		
Jet boundary layer	Lee	48
Satellite formation	Pimbley	21
Ink jet technology		
Ink drop charging and deflection	Fillmore	37
Ink jet printer materials	Beach	75
Ink jet scale model	Curry	10
Ink jet scale-up model	Levanoni	56
Ink jet printer technology	Buehner	2
Ink jet variable tolerances	Twardeck	31
Jet boundary layer	Lee	48
Jet printer ink	Ashley	69
Print height control (C)	Carmichael	52
Satellite formation	Pimbley	21
Splatter during printing	Zable	315
Magnetic recording		
Dynamic response of strip (C)	Albrecht	379
Recording head measurements (C)	Feliss	289
Markov process analysis		
Network control	Chow	264
Materials		
Elastomeric block copolymers	Smith	154
Electron beam sensitivity of PMMA	Gipstein	143
Ink jet printer materials	Beach	75
Jet printer ink	Ashley	69
Negative ions in sputtering (C)	Cuomo	580
NMR study of P(MMA-co-MAA)	Lyerla	111
Photoresist analysis	Shaw	219
Photoresists	Dill	210
Polymer dissolution model	Tu	131
Polymeric properties by optical techniques	Swalen	168
Properties of $(SN)_x$	Street	99
Radiation chemistry of poly(methacrylate)	Hiraoka	121
Silicon nitride conduction	DiMaria	227
Single crystal garnet processing	Davies	522
Spin coating process	Washo	190
Sputtered Cr-SiO films (C)	Matino	576
Sulfur diffusion in polymers	Berry	176
Mathematics (applied)		
Bin packing	Kou	443

Comment on data base decomposition (L)	Delobel	484
Computations of lower bounds	Lang	273
Functional dependencies	Fagin	534
Jet boundary layer	Lee	48
Medical diagnosis	Peters	449
Number transforms	Nussbaumer	334
Radar images	van de Lindt	415
Satellite drop formation	Pimbley	21
Measurement		
Automatic registration	Davis	498
Capacitance probe study (C)	Feliss	289
Dynamic response of strip (C)	Albrecht	379
Ink jet scale model	Curry	10
Ink jet scale-up model	Levanoni	56
Ink jet splatter	Zable	315
Ink jet variable tolerances	Twardeck	31
Pattern recognition	Herbst	245
Regenerative simulation	Lavenberg	545
Memory structures		
Dynamic memories	Wong	281
Merged charge memory cell	Lee	402
Storage reorganization	Bennett	528
Models and modeling		
Ink jet scale model	Curry	10
Ink jet scale-up model	Levanoni	56
Neurons (C)	Traub	572
Optical science and technology		
Correction of nonlinear distortion	Engelke	506
Electron optics	Mauer	514
Laser-optical system (C)	Fleischer	479
Pattern recognition		
Signature verification	Herbst	245
Physical chemistry		
Negative ions in sputtering (C)	Cuomo	580
Physiology		
Medical diagnosis	Peters	449
Modeling neurons (C)	Traub	572
Polymer chemistry		
Elastomeric block copolymers	Smith	154
Electron beam sensitivity of PMMA	Gipstein	143
Kinematics of polymer dissolution	Tu	131
NMR study of P(MMA-co-MAA)	Lyerla	111
Polymeric thin films	Swalen	168
Properties of $(SN)_x$	Street	99
Radiation chemistry of poly(methacrylates)	Hiraoka	121
Sulfur diffusion in polymers	Berry	176
Programming and programming languages		
Comment on data base decomposition (L)	Delobel	484
Data flow analysis	Lomet	559
Language for mechanical assembly	Lieberman	321
SEQUEL 2 language (Vol. 20, No. 6) Erratum	Chamberlin	94
Quality control		
Ink drop charging and deflection	Fillmore	37
Ink jet splatter	Zable	315
Ink jet print height control (C)	Carmichael	52
Ink jet printing	Buehner	2
Ink jet variable tolerances	Twardeck	31
Laser-optical system (C)	Fleischer	479
Queuing theory		
Closed queuing networks (C)	Lam	384
Network priority assignments	Maruyama	254
Population size constraints	Lam	370
Erratum	Lam	598
Several packet classes	Maruyama	360
Solid state physics		
Merged charge memory cell	Lee	402
Safe operating area for bipolar transistors	Gaur	433
Silicon nitride conduction	DiMaria	227
Space-related technology		
Radar images	van de Lindt	415
Storage hierarchies		
Network control	Chow	264
Storage reorganization	Bennett	528

Erratum

In the article "Queuing Networks with Population Size Constraints" (S. S. Lam, *IBM J. Res. Develop.*, Vol. 21, No. 4, July 1977), page 376 should be amended as follows: $\sigma_r(X_{il}^{+3})$ in Eq. (A2) and $\sigma_r(X_{il}^{-r})$ in Eq. (A3) should both be replaced by $\sigma_r(X_{il}^{+r})$.